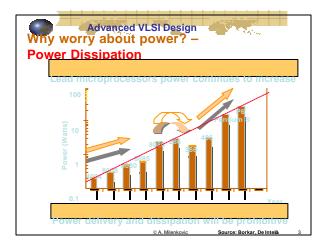


Advanced VLSI Design Why Power Matters

- Packaging costs
- Power supply rail design
- Chip and system cooling costs
- Noise immunity and system reliability
- Battery life (in portable systems)
- Environmental concerns
 - Office equipment accounted for 5% of total US commercial energy usage in 1993

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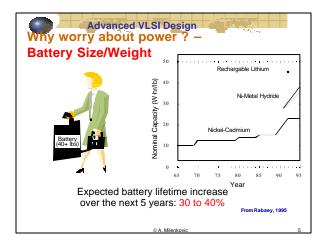
Energy Star compliant systems

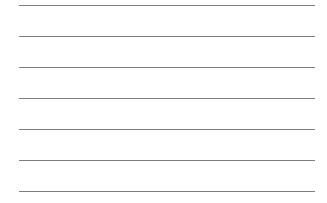


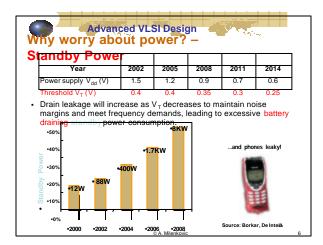




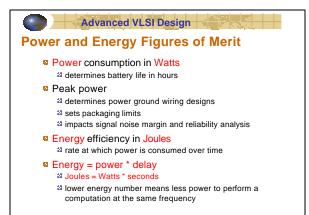




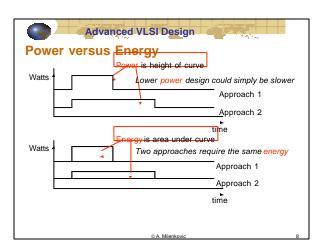




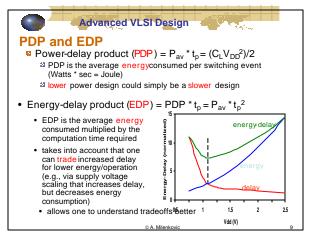


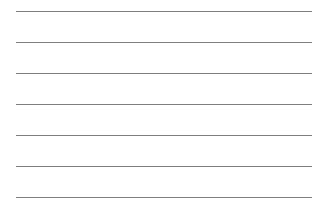


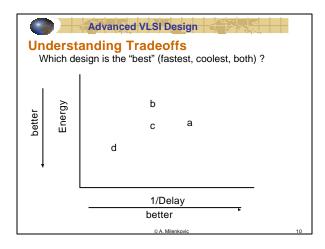
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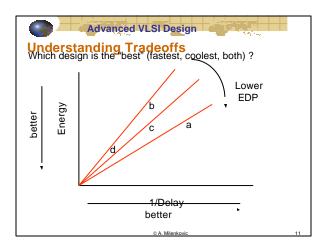




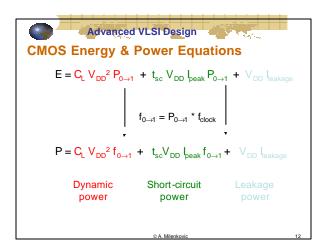




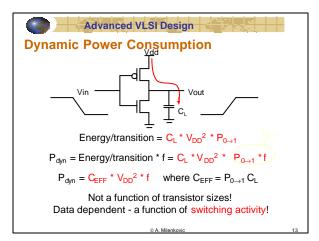




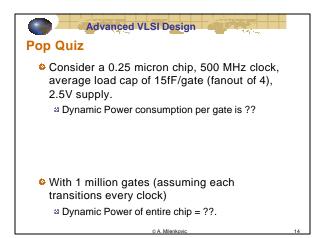


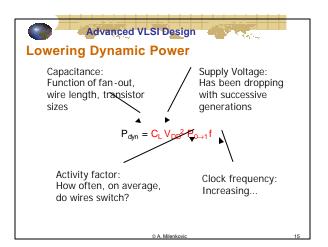




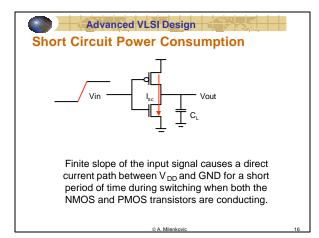


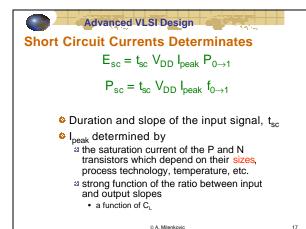


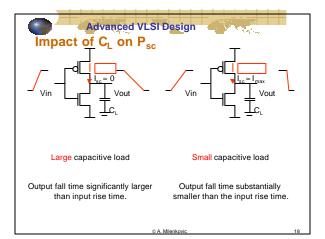




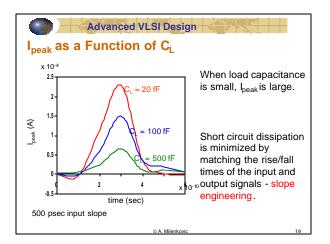




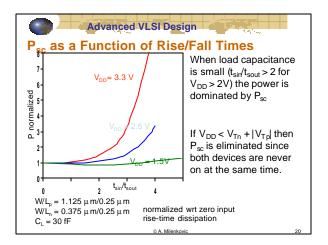


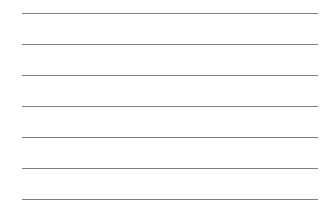


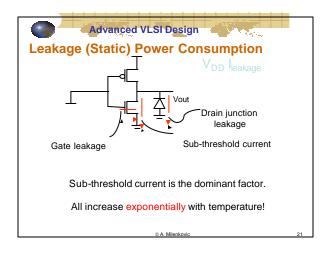




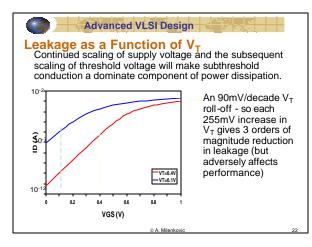




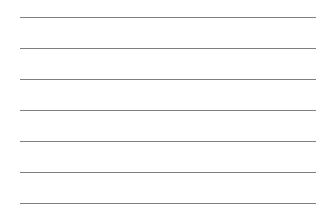


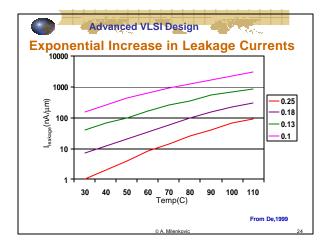




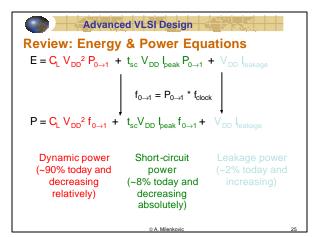


| | CL018 | CL018 | CL018 | CL018 | CL015 | CL013 |
|---|---------|---------|---------|---------|---------|---------|
| V _{dd} | 1.8 V | 1.8 V | 1.8 V | 2 V | 1.5 V | 1.2 V |
| T _{ox} (effective) | 42 Å | 42 Å | 42 Å | 42 Å | 29 Å | 24 Å |
| date | 0.16 µm | 0.16 µm | 0.18 µm | 0.13 µm | 0.11 µm | 0.08 µm |
| _{DSat} (n/p) (µA/µm) | 600/260 | 500/180 | 320/130 | 780/360 | 860/370 | 920/400 |
| l _{off} (leakage) (pA/μm) | 20 | 1.60 | 0.15 | 300 | 1,800 | 13,000 |
| V _{Tn} | 0.42 V | 0.63 V | 0.73 V | 0.40 V | 0.29 V | 0.25 V |
| FET Perf. | 30 | 22 | 14 | 43 | 52 | 80 |





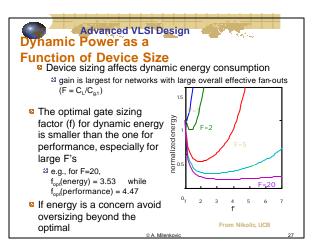


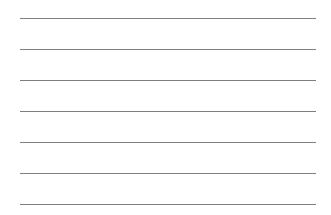


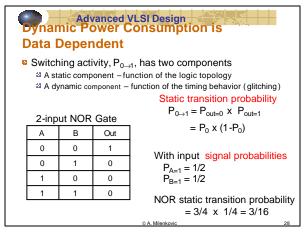


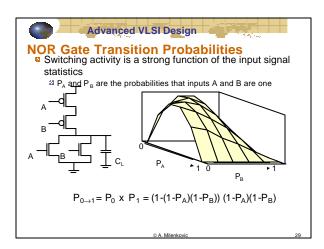
| | nd Energy Design Constant | | Variable | |
|---------|--|-------------------------------|-----------------|---|
| Energy | Design Time | | | put/Latency Run Time |
| Active | Reduced V _{dd} Sizing Multi V _{dd} | Clock Gating | | DFS, DVS (Dynamic Freq, Voltage Scaling) |
| Leakage | + Multi-V _T | Sleep Tra Multi- Variab | V _{dd} | + Variable V ₁ |
| | | | | |

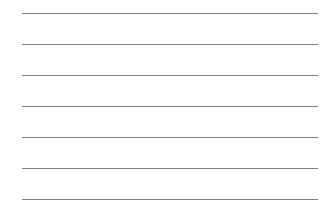


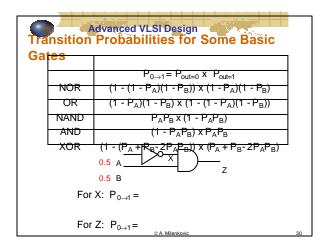


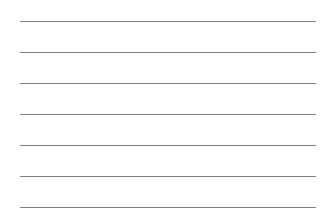






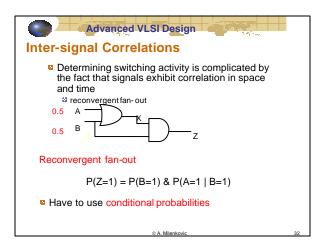


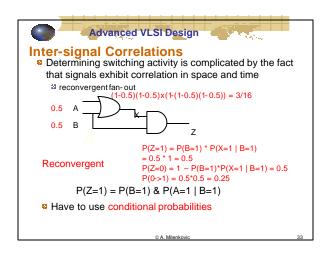


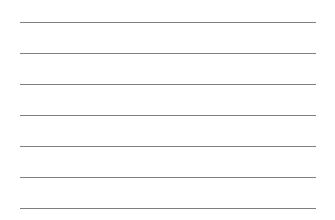


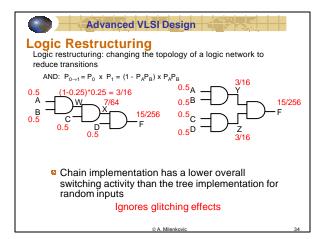
| Tra | | Advanced VLSI Design Probabilities for Some Basic | |
|-----|------|---|----|
| Ga | 105 | $P_{0 \rightarrow 1} = P_{out=0} \times P_{out=1}$ | |
| | NOR | (1 - (1 - P _A)(1 - P _B)) x (1 - P _A)(1 - P _B) | |
| | OR | (1 - P _A)(1 - P _B) x (1 - (1 - P _A)(1 - P _B)) | |
| | NAND | $P_A P_B x (1 - P_A P_B)$ | |
| | AND | $(1 - P_A P_B) \times P_A P_B$ | |
| | XOR | $(1 - (P_A + P_B - 2P_AP_B)) \times (P_A + P_B - 2P_AP_B)$ | |
| | | $\begin{array}{c c} 0.5 & A \\ \hline \\ 0.5 & B \\ \hline \\ \end{array} \\ \hline \\ \end{array} \\ \hline \\ \\ \\ \\ \\ \\ \\ \\ \\ \\$ | |
| | For | X: $P_{0\to1} = P_0 \times P_1 = (1-P_A) P_A$ = 0.5 x 0.5 = 0.25 | |
| | For | Z: $P_{0 \rightarrow 1} = P_0 \times P_1 = (1 - P_X P_B) P_X P_B$ = $(1 - (0.5 \times 0.5)) \times (0.5 \times 0.5) = 3/16$ | |
| | | © A. Milenkovic | 31 |



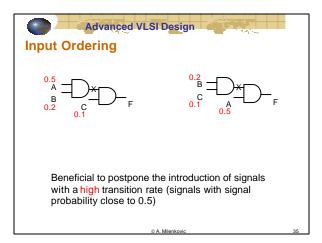


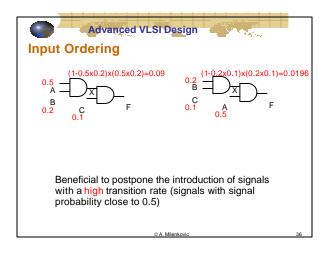






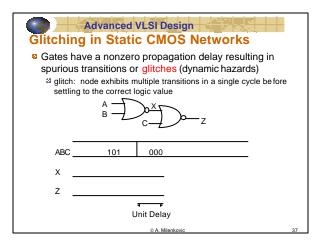




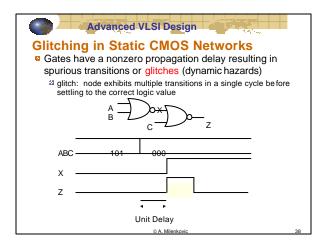




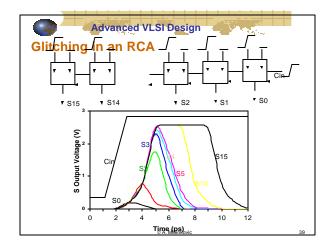




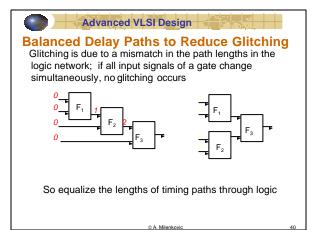






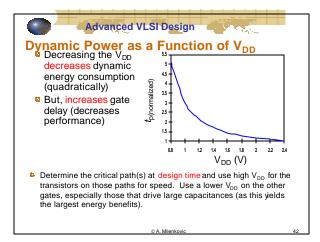




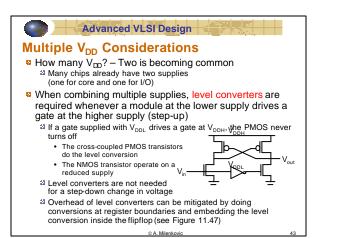


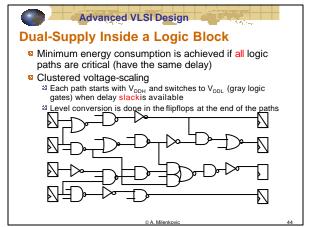
| Power a | Advanced V nd Energy | | - | | | |
|---------|--|---|---------|---|--|--|
| | Consta Throughput/ | | | Variable Throughput/Latency | | |
| Energy | Design Time | Non-active | Modules | Run Time | | |
| Active | Logic Design Reduced V _{dd} Sizing Multi V _{dd} | Clock Gating | | DFS, DVS (Dynamic Freq, Voltage Scaling) | | |
| Leakage | + Multi-V _T | Sleep Transistors Multi-V _{dd} Variable Vr | | + Variable V _T | | |
| | | | · | | | |

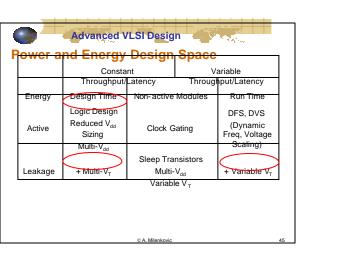




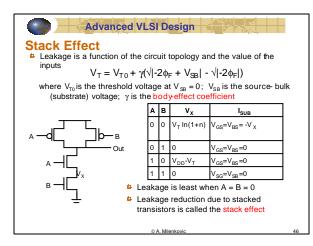


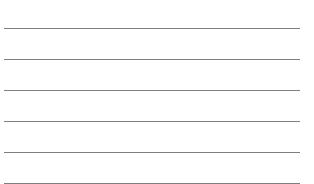










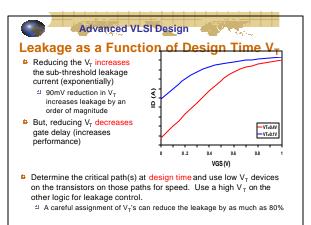


Advanced VLSI Design

Short Channel Factors and Stack Effect In short-channel devices, the subthreshold leakage current depends on V_{CS}, V_{BS} and V_{DS}. The V_T of a short-channel device decreases with increasing V_{DS} due to DIBL (drain-induced barrier loading). ⁴³ Typical values for DIBL are 20 to 150mV change in V_T per voltage change in V_{DS} so the stack effect is even more significant for short-channel devices. ⁴³ V_X reduces the drainsource voltage of the top nfet, increasing its V_T and lowering its leakage

^{III} For our 0.25 micron technology, V_X settles to ~100mV in steady state so V_{BS} = -100mV and V_{DS} = V_{DD} -100mV which is 20 times smaller than the leakage of a device with V_{BS} = 0mV and V_{DS} = V_{DD}

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